# David L. Windt

## *Education*

1987 Ph.D., Physics University of Colorado, Boulder
1985 M.S., Physics University of Colorado, Boulder
1982 B.S., Physics University of Connecticut, Storrs; *magna cum laude, Phi Beta Kappa*

## *Professional Experience*

2005 – *present* Founder and President, Reflective X-ray Optics LLC, New York, New York
2006 – *present* Adjunct Research Scientist, Columbia Astrophysics Laboratory, New York, New York
2000 – 2005 Research Scientist, Columbia Astrophysics Laboratory, New York, New York
1990 – 1999 Member of Technical Staff, Bell Labs, Lucent Technologies, Murray Hill, New Jersey
1998 Visiting Scholar, Dept. of Physics, New York University, New York
1989 Resident Visitor, AT&T Bell Laboratories, Murray Hill, New Jersey
1987 – 1989 Associate Research Scientist, Space Sciences Department, Lockheed Palo Alto Research Laboratory, Palo Alto, California
1982 – 1987 Graduate Research Assistant, Dept. of Physics, Laboratory for Atmospheric & Space Physics and Center for Astrophysics & Space Astronomy, University of Colorado, Boulder
1983 Teaching Assistant, Dept. of Physics, University of Colorado, Boulder
1982 Teaching Assistant, Dept. of Mechanical Engineering, University of Connecticut, Storrs

## *Professional Affiliations*

- American Astronomical Society
- American Physical Society
- Materials Research Society (past)
- Optical Society of America (past)
- Society of Photo-optical Instrumentation Engineers (past)

## *Conference Organization*

- Co-founder and co-organizer of the International Conference on the Physics of X-ray Multilayer Structures (PXRMS), held biennially from 1992 through 2010
- Co-organizer of the US-Japan workshop on EUV lithography, 1993

## *Patents*

7 patents relating to multilayer and thin-film technology with applications to photolithography, film deposition, and medical imaging.

## *Publications*

Numerous technical publications on thin films and multilayer coatings, X-ray astronomy, X-ray lithography and X-ray mammography. Two scientific software packages: IMD – for modeling and fitting specular and non-specular multilayer optical properties, and TOPO – for surface topography analysis.